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**IN THE CLAIMS:**

Please cancel claim 7 without prejudice or disclaimer of the subject matter thereof.

**Amendments to the Claims**

**Listing of Claims:**

This listing of claims will replace all prior versions, and listings, of claims in the application:

1. (currently amended) A plasma processing apparatus to provide plasma processing of a substrate by plasma, said plasma processing apparatus comprising a plasma processing gas supply means, an exhaust means in a plasma process chamber, and a plasma generating means, said plasma generating means further comprises:

a first capacitatively coupled plasma generating means; and

a second electromagnetic wave radiation plasma generating means;

wherein said first capacitatively coupled plasma means includes an opposed plate type electrode consisting of a plurality of mutually isolated conductors oppositely disposed with respect to a stage electrode and a single commonly shared high-frequency power supply means to supply for supplying said high-frequency power to said plurality of isolated conditions of said opposed electrode through a matching box, said first capacitatively coupled plasma generating means being arranged so that a capacitatively coupled plasma discharge is generated between said opposed electrode and said stage electrode;

wherein said second electromagnetic wave radiation plasma generating means comprises insulators disposed between at least a portion of a plasma process chamber which is grounded and said plurality of isolated conductors, respectively, said second electromagnetic wave radiation plasma generating means being arranged so that an electromagnetic wave is radiated from ~~at least a position~~